

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

In re Application of: Bradley J. Howard

Filed: Herewith

For: PROCESS FOR USING PHOTO-DEFINABLE LAYERS IN THE MANUFACTURE  
OF SEMICONDUCTOR DEVICES AND RESULTING STRUCTURES OF SAME

Serial No.: Unknown

Group Art Unit: Unknown

Examiner: Unknown

Atty Dkt: 97-0008.02

Pursuant to 37 C.F.R. 1.8, I certify that this correspondence is being deposited with the U.S. Postal Service in a first class, postage prepaid envelope addressed to: Assistant Commissioner for Patents, Washington, D.C. 20231 on the date below:

11-6-03

Dane C Potts

Date

Name

**INFORMATION DISCLOSURE STATEMENT**

Assistant Commissioner for Patents  
Washington, D.C. 20231

Sir:

Pursuant to 37 C.F.R. §§ 1.56, 1.97, and 1.98, it is respectfully requested that this Information Disclosure Statement be entered and the documents listed on attached Form PTO-1449 be considered by the Examiner and made of record.

In accordance with 37 C.F.R §§ 1.97(g),(h), this Information Disclosure Statement is not to be construed as a representation that a search has been made, and is not to be construed to be an admission that (a) the information cited is, or is considered to be, material to patentability as defined in 37 C.F.R. § 1.56(b); and/or (b) that the information cited is, or is considered to be prior art.

The present Information Disclosure Statement is being filed prior to the receipt of a first Official Action reflecting an examination on the merits, and hence is believed to be timely filed in accordance with 37 C.F.R. § 1.97(b). No fees are believed to be due in connection with the filing of this Information Disclosure Statement, however, should any fees under 37 C.F.R. §§ 1.16 to 1.21 be deemed necessary for any reason relating to these materials, the Commissioner is hereby authorized to deduct said fees from Deposit Account No. 10-1205.

Copies of the listed documents required by 37 C.F.R. § 1.98(a)(2) have been previously submitted in the parent application.

Applicant respectfully requests that the listed documents be made of record in the present case.

Respectfully submitted,



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Enclosures

<b>Form PTO-1449</b> (modified)		Atty. Docket No. 97-0008.02	Serial No. Unknown
List of Patents and Publications for Applicant's		Applicant Bradley J. Howard	
<b>INFORMATION DISCLOSURE STATEMENT</b>  (Use several sheets if necessary)		Filing Date: Herewith	
U.S. Patent Documents See Page 1	Foreign Patent Documents N/A		Other Art See Page 1

### U.S. Patent Documents

Exam. Init.	Ref. Des.	Document Number	Date	Name	Class	Sub Class	Filing Date if App.
	A1	4,921,321	5/1/90	Weidman			
	A2	5,439,780	8/8/95	Joshi et al.			
	A3	5,215,861	6/1/93	Augustino et al.			
	A4	4,978,594	12/18/90	Bruce et al.			
	A5	5,885,751	3/23/99	Weidman et al.			

### Foreign Patent Documents

Exam. Init.	Ref. Des.	Document Number	Date	Country	Class	Sub Class	Translation Yes/No
	B1						

### Other Art (Including Author, Title, Date Pertinent Pages, Etc.)

Exam. Init.	Ref. Des.	Citation
	C1	Ajey M. Joshi et al., "Plasma Deposited Organosilicon Hydride Network Polymers as Versatile Resists for Entirely Dry Mid-Deep UV Photolithography," <i>SPIE</i> , Vol. 1925, pp. 709-720, January 1993.
	C2	O. Joubert et al., "Plasma polymerized - dry resist process for 0.25 μm photolithography," <i>J. Vac. Sci. Technol. B</i> 12(6), pp. 3909-3913, Nov/Dec 1994.
	C3	O. Joubert et al., "Plasma Polymerized Organosilane Network Polymers; High Performance Resists for Positive and Negative Tone Deep UV Lithography," <i>SPIE</i> , Vol. 2195, pp. 358-371, May 1994.
	C4	T. W. Weidman et al., "Applications of Plasma Polymerized Methylsilane as a Resist and Silicon Dioxide Precursor for 193 and 248 nm Lithography," <i>SPIE</i> , Vol. 2438, pp. 496-512, June 1995.
	C5	Timothy W. Weidman and Ajey M. Joshi, "New photodefinable glass etch masks for entirely dry photolithography: Plasma deposited organosilicon hydride polymers," <i>Appl. Phys. Lett.</i> 62(4), pp. 372-374, January 25, 1993

Examiner:	Date Considered:
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EXAMINER: initial if reference considered, whether or not citation is in conformance with MPEP609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.